

基於推導線與重繞線的佈局密度優化方法 = Layout density optimization with wire pushing and rerouting for CMP planarization

陳冠中、林浩仁, 程仲勝

E-mail: 354784@mail.dyu.edu.tw

摘要

化學機械研磨(Chemical-Mechanical Polishing ; CMP)技術的形成是目前後端製程所必經的步驟，為了提高CMP程序後整體佈局的平坦度，需在晶片佈局中添加虛擬焊墊(Dummy Fill)填充。在安插虛擬焊墊至晶片佈局前，必須先對晶片佈局做密度分析，並計算需要安插多少虛擬焊墊數量置晶片佈局的。本文提出推導線與重繞線方法，以減少降低初始晶片佈局密度不均勻的情況，固定分割在計算安插多少虛擬焊墊數量至方格(Tile)中，會有為了提昇平坦度目標，而造成虛擬焊墊數量上使用過多的情況發生，而本文提出推導線與重繞線方法，目的在可以降低虛擬焊墊的使用成本。以ISCAS89 測試電路的實驗數據顯示，本文提出的推導線與重繞線方法，可以節省虛擬焊墊使用數量達12%到22%。

關鍵詞：平坦化、CMP 平坦化技術、虛擬焊墊

目錄

封面內頁

簽名頁

中文摘要 iii

ABSTRACT v

誌謝 vi

目錄 vii

圖目錄 ix

表目錄 x

第一章 緒論 1

1.1研究背景 1

1.2研究動機 4

1.3研究目的 6

1.4論文大綱 8

第二章 文獻回顧 9

2.1化學機械研磨技術 9

2.2平坦化方法 10

2.3推導線與繞線 12

第三章 推導線與重繞線方法 15

3.1佈局畫分成tiles之流程 17

3.2推導線流程 20

3.3重繞線流程 22

第四章 實驗結果 25

4.1實驗環境與測試電路 25

4.2實驗結果 26

第五章 結論與未來展望 38

5.1結論 38

5.2未來展望 38

參考文獻 39

參考文獻

[1] <http://zh.wikipedia.org/wiki/%E6%91%A9%E5%B0%94%E5%AE%9A%E5%BE%8B>.

- [2]Chen, Y., A. B. Kahng, G. Robins and A. Zelikovsky, "Area fill synthesis for uniform layout density," IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, 21(10), 1132-1147.
- [3]Chen, Y., A. B. Kahng, G. Robins and A. Zelikovsky, "Closing the smoothness and uniformity gap in area fill synthesis," Proceedings of the 2002 International Symposium on Physical Design, San Diego, CA.
- [4]He, L., A. B. Kahng, K. Tam and J. Xiong, "Simultaneous buffer insertion and wire sizing considering systematic CMP variation and random leff variation," Proceedings of the 2005 International Symposium on Physical Design, San Francisco, CA.
- [5]Kahng, A. B., G. Robins, A. Singh and A. Zelikovsky, "Filling algorithms and analyses for layout density control," IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, 18(4), 445-462.
- [6]Kahng, A. B. and K. Samadi, "CMP fill synthesis: A survey of recent studies," IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, 27(1), 3-18.
- [7]Tian, R., D. F. Wong and R. Boone, "Model-based dummy feature placement for oxide chemical-mechanical polishing manufacturability," Proceedings of the 37th Annual Design Automation Conference, Los Angeles, CA.
- [8]Tian, R., D. F. Wong and R. Boone, "Model-based dummy feature placement for oxide chemical-mechanical polishing manufacturability," IEEE Transactions on Computer Aided Design of Integrated Circuits and Systems, 20(7), 902-910.
- [9]Xiang, H., K. Y. Chao, R. Puri and M. D. F. Wong, "Is your layout density verification exact?," A fast exact algorithm for density calculation. IEEE Transactions on.
- [10]A. B. Kahng, G. Robins, A. Singh, and A. Zelikovsky, "Filling algorithms and analyses for layout density control," IEEE Trans. Computer-Aided Design Integrated. Circuits and systems, vol. 18, no. 4, pp. 445 – 462, Apr. 1999.
- [11]T. E. Gbondo. Tugbawa, "Chip-Scale Modeling of Pattern Dependencies in Copper Chemical Mechanical Polishing Process," Ph.D. dissertation, Massachusetts Institute of Technology, 2002.
- [12]Modeling of On Chip Transmission Lines — Impact of Orthogonal Wires, Si Substrate and Dummy Fills—. SPI 2006, SIGNAL PROPAGATION ON INTERCONNECTS.
- [13]Y. Chen, A. B. Kahng, G. Robins and A. Zelikovsky, "Area Fill Synthesis for Uniform Layout Density", IEEE Trans. on Computer-Aided Design of Integrated Circuits and Systems, vol. 21, Oct. 2002.
- [14]Y. Chen, A. B. Kahng, G. Robins, and A. Zelikovsky, "Monte-Carlo algorithms for layout density control," in Proc. IEEE Asia South Pacific Des. Autom. Conf., 2000, pp. 523 – 528.
- [15]Y. Chen, P. Gupta, and A. B. Kahng, "Performance impact limited area fill synthesis," in Proc. ACM/IEEE Des. Autom. Conf., 2003, pp. 22 – 27.
- [16]H. Xiang, L. Deng, R. Puri, K. Y. Chao, and M. D. F. Wong, "Dummy fill density analysis with coupling constraints," in Proc. ACM/IEEE Int. Symp. Phys. Des., 2007, pp. 3 – 9.
- [17]Yu Chen, Andrew B. Kahng, Gabriel Robins, Alexander Zelikovsky, Yuhong Zheng, Area Fill Generation With Inherent Data Volume Reduction, Proceedings of the conference on Design, Automation and Test in Europe, p.10868, March 03.07, 2003.
- [18]Y. Chen, A. B. Kahng, G. Robins, A. Zelikovsky, and Y. Zheng, "Compressible area fill synthesis," IEEE Trans. Computer-Aided Design of Integrated Circuits Syst., vol. 24, no. 8, pp. 1169 – 1187, 2005.
- [19]L. He, A. B. Kahng, K. Tam and J. Xiong, "Simultaneous Buffer Insertion and Wire Sizing Considering Systematic CMP Variation and Random Leff Variation," in Proc. of the 2005 International Symposium on Physical Design, April 2005, pp. 78 – 85.
- [20]Hua Xiang, Xiaoping Tang, and Martin D. F. Wong, "Min Cost Flow Based Algorithm for Simultaneous Pin Assignment and Routing," IEEE TRANSACTIONS ON COMPUTER-AIDED DESIGN OF INTEGRATED CIRCUITS AND SYSTEMS, VOL. 22, NO. 7, JULY 2003, pp. 870 – 878.
- [21]Cheok. Kei Lei, Bo. Yi Chiang and Yu. Min Lee, "An Efficient Redundant Via Insertion with Wire Pushing Capability," in Proceedings of the 19th VLSI Design/CAD Symposium, 2008.
- [22]Ed. P. Huijbregtsl, Jos T. J. van Eijndhoven and Jochen A. G. Jess, "On Design Rule Correct Maze Routing," in Proceedings of the European Design and Test Conference, EDAC, MAR 1994, pp. 407 – 411.
- [23] <http://ic.engin.brown.edu/classes/EN160S07/lecture27.ppt>.
- [24] <http://users.eecs.northwestern.edu/~haizhou/357/lec6.pdf>.
- [25]林宗輝、馬光華,「方興未艾之可製造性導向設計」,台灣半導體產業協會簡訊專文,2005/7。
- [26]陳冠中、嚴文宏、林浩仁,「CMP佈局平坦化的階層式密?分析方法」,科學與工程技術期刊,第?卷 第二期 民國九十九?, pp.1-8。